

What is claimed is:

1. (Amended) A processing device comprising:

a chamber (12) defining a processing area;

a mounting table (16), disposed in the chamber (12),
for mounting thereon an object to be processed; and

a gas supply port (19) for supplying a gas into the
chamber (12), the gas supply port (19) being provided at a
surface (12b) of the chamber (12);

wherein the mounting table (16) is disposed
substantially parallel to the surface (12b) of the chamber
(12); and

in a substantially vertical cross section of the
chamber (12) taken along a flow of the gas from the gas
supply port (19) toward the object to be processed, a
sidewall (12d) of the chamber (12) defining the processing
area and abutting on the surface (12b) of the chamber forms
an angle greater than 90° with the surface (12b) of the
chamber and extends close to the mounting table 16.

2. The processing device of claim 1, wherein the gas
supply port (19) is configured to have a substantially same
area as that of the object to be processed.

3. The processing device of claim 1, wherein in a
substantially vertical cross section of the mounting table

(16) taken along the flow of the gas from the gas supply port (19) toward the object to be processed, a mounting surface on which the object to be processed is mounted forms an angle greater than 90° with a side surface of the mounting table (16) abutting on the mounting surface.

4. The processing device of claim 3, wherein in a substantially vertical cross section of the chamber (12) and the mounting table (16) taken along the flow of the gas from the gas supply port (19) toward the object to be processed, the sidewall (12d) of the chamber is configured to be substantially parallel to the side surface of the mounting table (16).

5. The processing device of claim 4, wherein in a substantially vertical cross section of the chamber (12) and the mounting table (16) taken along the flow of the gas from the gas supply port (19) toward the object to be processed, the distance between the sidewall (12d) of the chamber and the side surface of the mounting table (16) is set to be less than the distance between the surface (12b) of the chamber and the object to be processed.

6. (Amended) A processing device comprising:

a chamber (12) defining a processing area;

a mounting table (16), disposed in the chamber (12),

for mounting thereon an object to be processed; and

a gas supply port (19) for supplying a gas into the chamber (12), the gas supply port (19) being provided at a surface (12b) of the chamber (12);

wherein the mounting table (16) is disposed substantially parallel to a flow direction of the gas supplied from the gas supply port (19); and

in a substantially vertical cross section and/or a substantially horizontal section of the chamber (12), a sidewall (12d) of the chamber (12) defining the processing area and abutting on the surface (12b) of the chamber forms an angle greater than 90° with the surface (12b) of the chamber and extends close to the mounting table 16.

7. (Amended) A processing device comprising:

a chamber (12) defining a processing area;

a mounting table (16), disposed in the chamber (12), for mounting thereon an object to be processed;

a gas supply port (19) for supplying a gas into the chamber (12), the gas supply port (19) being provided at a surface (12b, 12a) of the chamber (12); and

a gas exhaust port (13) for evacuating the chamber (12);

wherein at least one of sidewalls (12d, 12aa) of the chamber (12) defining the processing area and abutting on one surface (12b, 12a) of the chamber (12) forms an angle

greater than 90° with said one surface (12b, 12a) of the chamber (12) and extends close to at least a portion of an outer surface of the object to be processed;

the gas flows a flow passageway whose cross sectional area is gradually increased from the gas supply port (19) to a proximal end of the object to be processed and is gradually decreased from a distal end of the object to be processed to the gas exhaust port (13).

8. (Canceled)

9. (Canceled)

10. (New) A processing device comprising:

a chamber (12) defining a processing area;

a mounting table (16), disposed in the chamber (12), for mounting thereon an object to be processed; and

a gas supply port (19) for supplying a gas into the chamber (12), the gas supply port (19) being provided at a surface (12b) of the chamber (12);

wherein in a substantially vertical cross section of the chamber (12) taken along a flow of the gas from the gas supply port (19) toward the object to be processed, a sidewall (12d) of the chamber (12) defining the processing area and abutting on the surface (12b) of the chamber extends slant at an angle greater than 90° with respect to

the surface (12b) of the chamber to be close to the mounting table 16; and

a side surface of the mounting table 16 is configured to match the slant of the sidewall (12d).